

ABSTRACT OF THE DISCLOSURE

An exposure apparatus for aligning a substrate and performing exposure using the aligned substrate. The apparatus includes a first alignment system, having a first stage and a first image sensing unit, to detect a position of a first mark on the substrate on the first stage using the first image sensing unit, a transfer system to transfer the substrate, on which the position of the first mark has been detected by the first alignment system, from the first stage onto a second stage, and a second alignment system, having the second stage and a second image sensing unit of which magnification is higher than that of the first image sensing unit, to detect a position of a second mark on the substrate on the second stage using the second image sensing unit, and to align the substrate based on the detection obtained by using the second image sensing unit. The first and second alignment systems and the transfer system are arranged such that the second mark on the substrate transferred on the second stage is positioned within a view of the second image sensing unit.